L Number	Hits	Search Text	DB	Tim stamp
-	165	((mon crystal or monocrystalline) near2 substrate) and (amorphou n ar oxide) and (metal near (oxide r nitride)) and ((cap r capping) adj layer) and (template adj lay r) and oxide.clm. and oxide.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:41
-	150	((monocrystal or monocrystalline) near2 substrate) and (amorphous near oxide).clm. and (metal near (oxide or nitride)) and ((cap or capping) adj layer) and (template adj layer) and oxide.clm. and oxide.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:42
-	23	((monocrystal or monocrystalline) near2 substrate) and (amorphous near oxide).clm. and (metal near (oxide or nitride)) and ((cap or capping) adj layer).clm. and (template adj layer) and oxide.clm. and oxide.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:42
-	5	((monocrystal or monocrystalline) near2 substrate) and (amorphous near oxide).clm. and (metal near (oxide or nitride)).clm. and ((cap or capping) adj layer).clm. and (template adj layer) and oxide.clm. and oxide.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:42
-	23	((monocrystal or monocrystalline) near2 substrate) and (amorphous near oxide).clm. and (metal near (oxide or nitride)) and ((cap or capping) adj layer).clm. and (template adj layer) and oxide.clm. and oxide.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:49
-	12	((monocrystalline or monorystal) near2 (substrate)) same (amorphous near2 oxide) same (metal near (oxide or nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:51
-	6	((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. same (metal near (oxide or nitride)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:52
-	20	((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and (metal near (oxide or nitride)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:53
-	194	((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:53
-	30	((m n rystalline or monorystal) near2 (substrate)).clm. and (am rph us near xide).clm. and ((cap or capping) adj layer).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:53

-	30	((mon crystalline or monorystal) near2 (substrate)). lm. and (amorph us n ar oxide).clm. and ((cap r apping) adj lay r).clm. and template	USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:55
-	188	((m n crystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:55
-	34	((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:55
-	0	(((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping)).clm.) not (((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:55
-	154	(((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping))) not (((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping)).clm.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/01/29 16:55
-	4	(((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping)).clm.) not (((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping) adj layer).clm. and template)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/02 14:03
-	34	(((monocrystalline or monorystal) near2 (substrate)).clm. and (amorphous near oxide).clm. and ((cap or capping)).clm.) and (template or (compound near semiconductor)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/02 14:04